	Application No.	Applicant(s)
Nation of Allowahility	10/805,670	HOFMANN ET AL.
Notice of Allowability	Examiner	Art Unit
	David Nhu	2818
The MAILING DATE of this communication appeal All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this applied or other appropriate communication IGHTS. This application is subject to	plication. If not included will be mailed in due course. THIS
1. This communication is responsive to <u>12/22/06</u> .		·
2. The allowed claim(s) is/are <u>18-37</u> .		
 3. Acknowledgment is made of a claim for foreign priority una) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 1. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have 1. Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" on oted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 4. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give 5. CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftsperson to Paper No./Mail Date 	been received. been received in Application No cuments have been received in this communication to file a reply ENT of this application. itted. Note the attached EXAMINER' es reason(s) why the oath or declarant be submitted. on's Patent Drawing Review (PTO-	complying with the requirements S AMENDMENT or NOTICE OF tion is deficient.
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	s Amendment / Comment or in the O	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	.84(c)) should be written on the drawir ne header according to 37 CFR 1.121(c	ngs in the front (not the back) of d).
 DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT F 	sit of BIOLOGICAL MATERIAL n FOR THE DEPOSIT OF BIOLOGICA	nust be submitted. Note the AL MATERIAL.
Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. ☐ Notice of Informal P. 6. ☐ Interview Summary Paper No./Mail Dat 7. ☒ Examiner's Amenda 8. ☒ Examiner's Stateme 9. ☐ Other	(PTO-413), e nent/Comment ent of Reasons for Allowance

EXAMINER'S AMENDMENT

1. Applicant's election of claims **20-37** is acknowledged. Because Applicant did not distinctly and specifically point out the supposed error in the restriction requirement,

the election has been treated as an election without traverse (MPEP § 818.03(a)).

Applicant have the right to file a divisional application covering the subject matter of the non-elected claim 38.

The traversal is on the ground(s) that see the election paper. This is not found persuasive because the fields of search for method' and device claims are NOT coextensive and the determinations of patentability of method and device claims are different, that is process limitations and device limitations are given weight differently in determining the patentablitity of the claimed inventions. Also, the strategies for doing text searching of the device claims and method claims are different. Thus, separate searches are required.

The requirement is still deemed proper and is therefore made FINAL.

2. An examiner's amendment to the record appears below. Should the change and/or additions be unaceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Cancel claims 1-19, 38.

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Claim 1, "wherein through the second gate electrode an electrical charge transmission of the multiple tunnel barrier arrangement can be controlled" should be -- wherein through the second gate electrode an electrical charge transmission of the multiple tunnel barrier arrangement is controlled-- Because "can" should not use in the claim.

REASONS FOR ALLOWANCE

- 3. Claims 20-37 are allowed.
- 4. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests a cited in claims 20, 35: forming a first trench structure in the layer system, the first trench structure having first trenches arranged parallel to one another and extending as far a the first electrically insulating layer; forming a second trench structure in the layer system, the second trench structure having second trenches arranged parallel to one another and extending as far as the first electrically insulating layer, the second trenches being arranged perpendicular to the first electrode; forming, in the first and second trench structures, a first gate electrode adjacent to the floating gate through which first gate electrode electrical charge is fed or dissipated from; and forming, in the first and second trench structures, a second gate electrode adjacent to the multiple tunnel barrier arrangement, wherein through the second gate electrode, an electrical charge transmission of the multiple barrier arrangement is controlled (as cited in claim 20); A method for operating a semiconductor memory element arrangement having a first electrically insulating layer formed on a substrate and a layer system comprising a floating gate and a tunnel barrier arrangement formed on the floating gate, the layer system being formed on the first electrically insulating layer and forming a multiple tunnel barrier, wherein first and second gate electrodes are formed in a first trench

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structure formed in the layer system, the first trench structure including first trenches arranged

parallel to one another and extending as far as the first electrically insulating layer, and a

second trench structure formed in the layer system, the second trench structure including

second trenches arranged parallel to one another and perpendicular to the first trenches and

extending as far as the first electrically insulating layer, the method comprising: reading an

electrical potential on the floating gate via the first gate electrode; and controlling an electrical

charge transmission of the tunnel barrier arrangement via the second gate electrode (as cited

in claim 35).

5. Any comments considered necessary by applicant must be submitted no later than the

payment of the issue fee and, to avoid processing delays, should preferably accompany the

issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons

for Allowance."

CONCLUSION

6. The prior art made of record and not relied upon is considered pertinent to applicant's

disclosure: Noble et al (5,973,356): Ultra High Density Flash Memory.

7. Any inquiry concerning this communication on earlier communications from the examiner

should be directed to David Nhu, (571)272-1792. The examiner can normally be reached

on Monday-Friday from 7:30 AM to 5:00 PM.

The fax phone number for the organization where this application or proceeding is assigned is

(571)273-8300.

David Nhu

Pa

January 19, 2007

DAVID NH

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PRIMARY





